

B.Tech III Year I Semester (R15) Regular Examinations November/December 2017

MEMS & MICROSYSTEMS

(Electronics & Communication Engineering)

Time: 3 hours

Max. Marks: 70

PART – A

(Compulsory Question)

- 1 Answer the following: (10 X 02 = 20 Marks)
- What is micromachining?
 - What is meant by Seebeck effect?
 - List the limitations of doping selective etching.
 - Mention the merits of surface micromachining.
 - List the types of mechanical microsensors.
 - What is meant by differential temperature technique?
 - Define mass ratio of propulsion system.
 - Define damping factor of second order system.
 - List out the applications of carbon nanotubes.
 - List the advantages of plastics.

PART – B

(Answer all five units, 5 X 10 = 50 Marks)

UNIT – I

- 2 Explain in detail about Silicon-Compatible material system.

OR

- 3 Discuss the effect of piezoresistivity and piezoelectricity.

UNIT – II

- 4 (a) Explain in detail about chemical vapor deposition and its applications.
(b) Explain the steps involved in lithography using lift-off technique.

OR

- 5 (a) Discuss about microstereolithography for MEMS.
(b) Write short notes on quartz micromachining.

UNIT – III

- 6 (a) Explain in detail about MEMS pressure sensors with neat diagrams.
(b) Write short notes on Bolometer detector.

OR

- 7 (a) Discuss the design aspects of flow sensor using the thin film anemometer.
(b) Explain the basic principle of micro-gyrometer.

UNIT – IV

- 8 (a) Explain the temperature drift in piezoresistive accelerometer.
(b) Write notes on micro machined tunneling accelerometer.

OR

- 9 Explain the basic principle and performance of capacitive accelerometer.

UNIT – V

- 10 (a) Discuss the features, issues and challenges of polymer MEMS.
(b) Explain the silicon fusion bonding mechanism.

OR

- 11 (a) Explain the role of interfacing electronics with integrated MEMS sensors.
(b) Write notes on Bio-MEMS.
